## UNITED STATES PATENT AND TRADEMARK OFFICE CERTIFICATE OF CORRECTION

PATENT NO.

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Page 1 of 1

DATED

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INVENTOR(S)

: June 6, 2006 : Rayssac

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

## Column 10:

Line 28 (claim 6, line 2), after "the plasma are Si and SF<sub>6</sub>, SiC and SF<sub>6</sub>/O<sub>2</sub>," insert -- SiO<sub>2</sub> --.

Line 58 (claim 14, line 5), after "clusters that is directed to" delete "is directed to".

## Column 11:

Line 9 (claim 17, line 4), after "controlled number of" delete "ion sin" and insert -- ions in --.

Signed and Sealed this

Twenty-seventh Day of March, 2007

JON W. DUDAS

Director of the United States Patent and Trademark Office